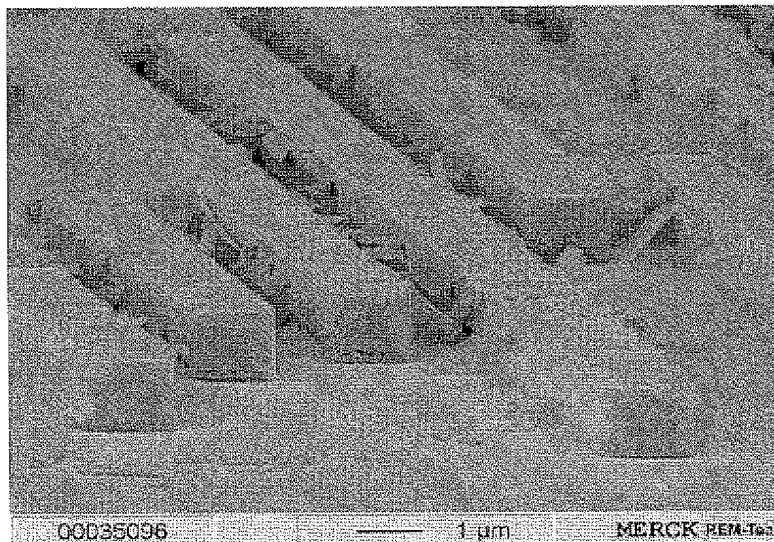


"REPLACEMENT SHEET"

Fig. 3

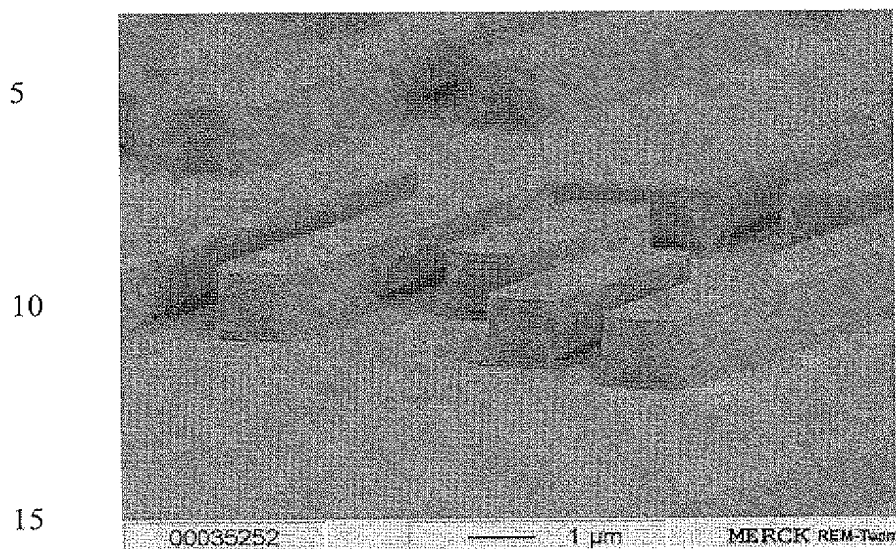
Residual polymers unstripped



"REPLACEMENT SHEET"

Fig. 4

After stripping with 100 ppm of H_2SiF_6



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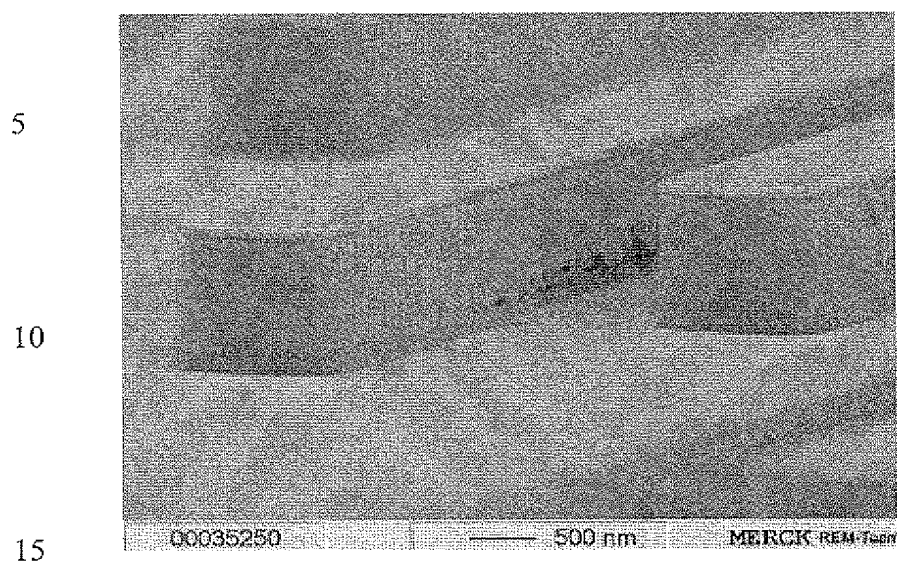
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"REPLACEMENT SHEET"

Fig. 5

After stripping with 500 ppm of H_2SiF_6



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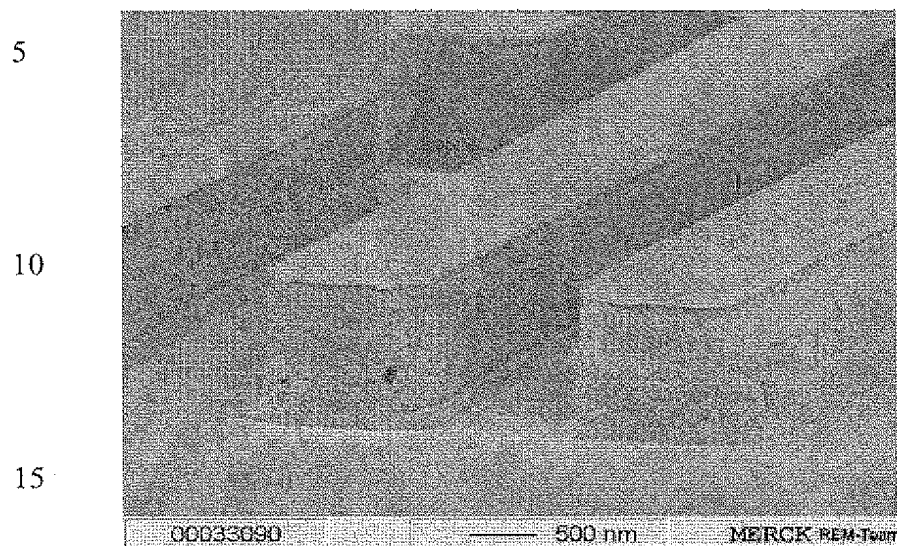
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"REPLACEMENT SHEET"

Fig. 6

After stripping with 1000 ppm of H_2SiF_6



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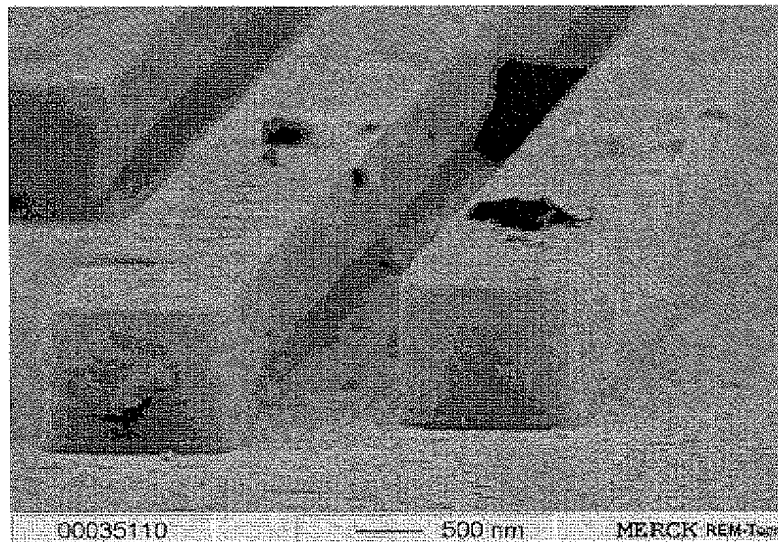
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"REPLACEMENT SHEET"

Fig. 7

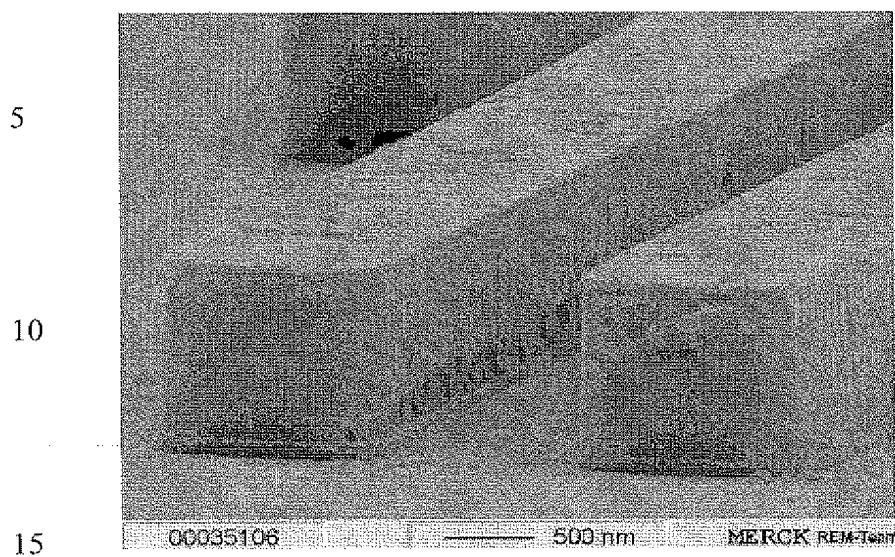
After stripping with 100 ppm of HF



"REPLACEMENT SHEET"

Fig. 8

After stripping with 200 ppm of HF



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"REPLACEMENT SHEET"

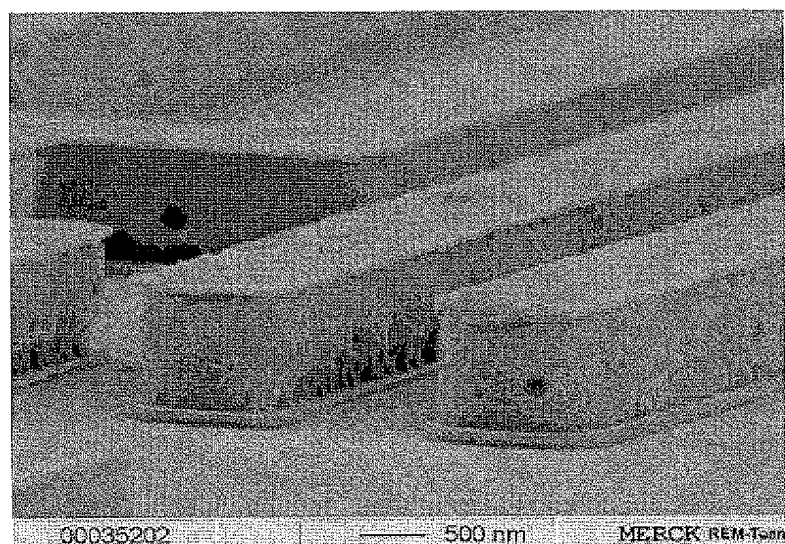
Fig. 9

After stripping with 500 ppm of HF

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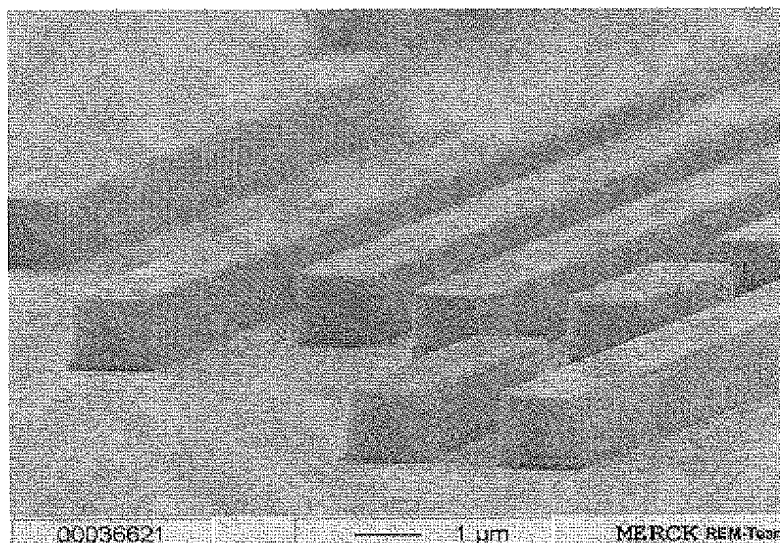
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"REPLACEMENT SHEET"

Stripping results in a Mattson AWP tank processor with various H_2SiF_6 concentrations.

Fig. 10

After stripping with 100 ppm of H_2SiF_6



"REPLACEMENT SHEET"

Fig. 11

After stripping with 600 ppm of H_2SiF_6

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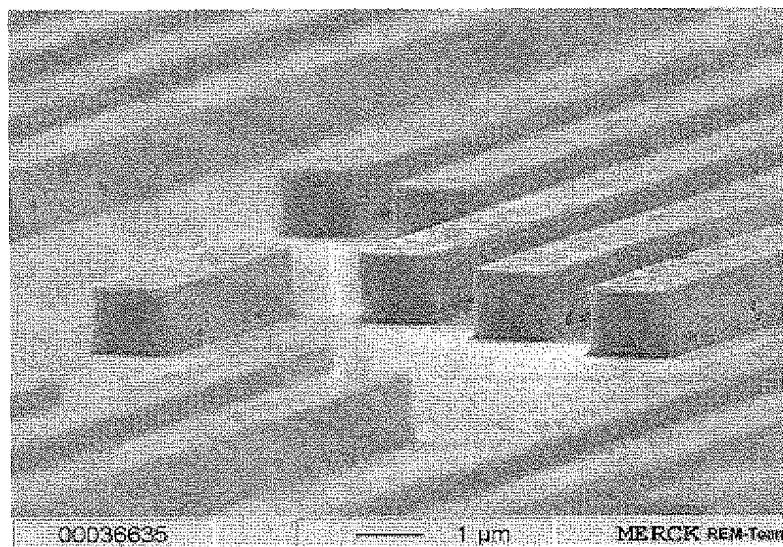
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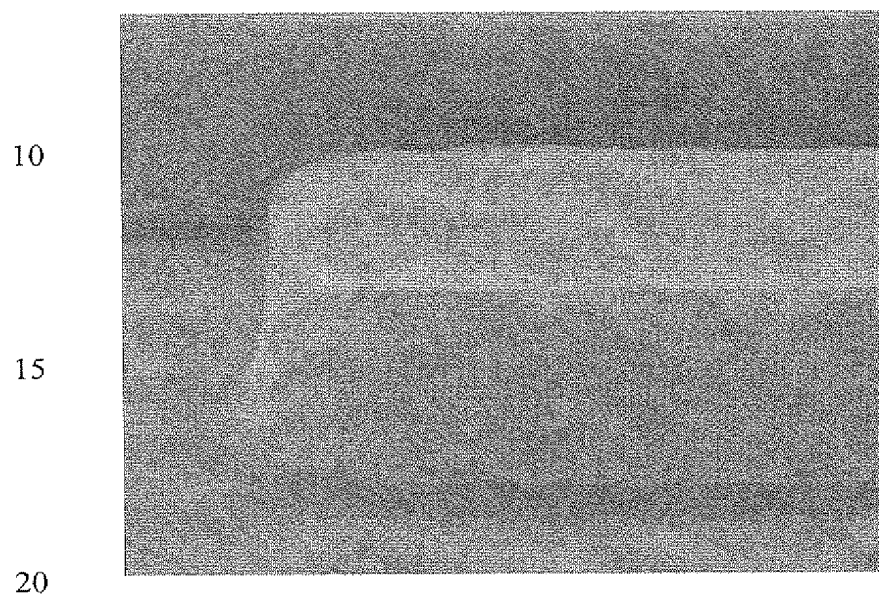
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"REPLACEMENT SHEET"

5 **Fig. 12:** Result after use of a composition with added surfactant.



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"REPLACEMENT SHEET"

Fig. 13

Comparison with Fig. 12: Result after use of a composition without added surfactant.

